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PATENT
2224-163P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: NAKANO, Tatsuya

Int'l. Appl. No.: PCT/JP99/02637

Appl. No.: New Group:

Filed: January 19, 2000 Examiner:

For: ACID-SENSITIVE COMPOUND AND RESIN
COMPOSITION FOR PHOTORESIST

#3a
N801

PRELIMINARY AMENDMENT

BOX PATENT APPLICATION

Assistant Commissioner for Patents
Washington, DC 20231

January 19, 2000

Sir:

The following Preliminary Amendments and Remarks are respectfully submitted in connection with the above-identified application.

AMENDMENTS

IN THE SPECIFICATION:

Please amend the specification as follows:

Before line 1, insert --This application is the national phase under 35 U.S.C. § 371 of PCT International Application No. PCT/JP99/02637 which has an International filing date of May 20, 1999, which designated the United States of America.-

PL

IN THE CLAIMS:

Please amend the claims as follows:

Claim 13: Line 2, change "8" to -10-

Claim 14: Line 3, change "8" to -10-

REMARKS

The specification has been amended to provide a cross-reference to the previously filed International Application.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fees required under 37 C.F.R. § 1.16 or under 37 C.F.R. § 1.17; particularly, extension of time fees.

Respectfully submitted,

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By 
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